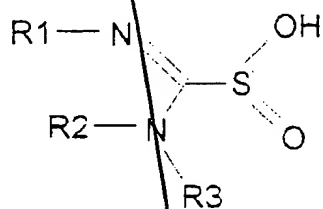


CLAIMS

1. Reducing composition for the permanent deformation of the hair, characterized in that it comprises, as reducing agent, an N-substituted formamidinesulphonic acid derivative of following general formula (I):



(I)

in which:

- (a) R1, R2 and R3, which are identical or different, represent a hydrogen atom, an amino, C1 to C8 aminoalkyl, imino, C1 to C8 aminoalkyl or guanidino group, a C1 to C8 linear or branched alkyl, C2 to C8 alkenyl or C7 to C20 aralkyl group, or an aromatic or nonaromatic C3 to C20 ring optionally comprising one or more heteroatom(s) chosen from halogens, nitrogen, oxygen or sulphur; it being possible for all these substituents optionally to carry one or more hydroxyl, carboxyl, amino, amido, halogen, C1-C8 alkyl or C1-C8 alkoxy radicals, and
- (b) at least one of the R1, R2 or R3 groups is an amino or C1 to C8 aminoalkyl group or is chosen from the

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alkyls, alkenyls, aralkyls, aryls or rings listed above in (a), these groups being, in addition, either directly substituted by at least one sulphonyl, sulphonate, phosphonyl, phosphate, amino or C1 to C8 alkoxy radical or substituted by another C1 to C8 alkyl, C2 to C8 alkenyl or C7 to C20 aralkyl group, themselves substituted by a sulphonic acid, sulphonate, phosphoric acid, phosphate, amino or C1 to C8 alkoxy radical;

10 and the inorganic or organic salts of the said compounds of formula (I).

2. Composition according to Claim 1, characterized in that the R1, R2 and R3 groups are selected from:

- 15 - the hydrogen atom,
- linear or branched C1-C6 alkyls optionally substituted by at least one hydroxyl, carboxyl, amino, sulphonyl or phosphonyl radical,
- phenyls optionally substituted by at least one
- 20 halogen atom or by a C1-C4 alkyl or C1-C4 alkoxy radical or alternatively hydroxyl,
- heterocycles, such as pyridine, dihydropyridine, tetrahydropyridine or quinoline, and
- the guanidino radical.

25 3. Composition according to Claim 1, characterized in that the compound of general formula (I) is chosen from:

- imino(methylamino)methanesulphinic acid

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- imino(propylamino)methanesulphinic acid
 - (dimethylamino)iminomethanesulphinic acid
 - (diethylamino)iminomethanesulphinic acid
 - (ethylamino)(ethylimino)methanesulphinic
 - 5 acid
 - (methylamino)(methylimino)methanesulphinic
 - acid
 - (ethylamino)(ethylimino)methanesulphinic
 - acid
 - 10 - (butylamino)(butylimino)methanesulphinic
 - acid
 - (phenylamino)(phenylimino)methanesulphinic
 - acid
 - (phenylmethylamino)(phenylmethylimino)-
 - 15 methanesulphinic acid
 - (carboxymethylamino)iminomethanesulphinic
 - acid
 - (2-carboxyethylamino)iminomethanesulphinic
 - acid
 - 20 - (3-carboxypropylamino)iminomethanesulphinic
 - acid
 - (5-carboxypentylamino)iminomethanesulphinic
 - acid
 - (hydroxymethylamino)iminomethanesulphinic
 - 25 acid
 - (2-aminoethylamino)iminomethanesulphinic
 - acid

- acid
- imino(sulphonylmethylamino)methanesulphinic acid
 - imino(2-sulphonylpropylamino)methane-sulphinic acid
 - 5 - imino(2-phosphonylmethylamino)methane-sulphinic acid
 - imino(phenylamino)methanesulphinic acid
 - imino(4-methylphenylamino)methanesulphinic acid
 - 10 - imino(4-hydroxyphenylamino)methanesulphinic acid
 - imino(4-methoxyphenylamino)methanesulphinic acid
 - imino(2-chlorophenylamino)methanesulphinic acid
 - 15 - imino(4-methyl-2-pyridylamino)methane-sulphinic acid
 - imino(6-methyl-2-pyridylamino)methane-sulphinic acid
 - 20 - imino(5-methyl-2-pyridylamino)methane-sulphinic acid
 - imino(2-quinolylamino)methanesulphinic acid
 - imino(3-quinolylamino)methanesulphinic acid
 - (methylimino)-2-pyridylaminomethane-
 - 25 sulphinic acid
 - (methylimino)[(3,4,5,6-tetrahydro-2-pyridyl)amino]methanesulphinic acid

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- [(aminoiminomethyl)amino]iminomethane-sulphinic acid.

4. Compound according to Claim 3, characterized in that the compound of general formula (I) is chosen from:

- (carboxymethylamino)iminomethanesulphinic acid, and
- imino(phenylamino)methanesulphinic acid.

5. Composition according to any one of the preceding claims, characterized in that the reducing agent of general formula (I) is present at a concentration of between 0.05 and 20% and preferably between 0.1 and 8% by weight with respect to the total weight of the reducing composition.

6. Composition according to any one of the preceding claims, characterized in that it exhibits a pH of between 2 and 11 and preferably between 7 and 10.

7. Composition according to any one of the preceding claims, characterized in that it additionally comprises an additive chosen from another known reducing agent, a surface-active agent of nonionic, anionic, cationic or amphoteric type, a treating agent of cationic, anionic, nonionic or amphoteric nature, fatty alcohols, lanolin derivatives, active ingredients, such as panthothenic acid, agents for combating hair loss, antidandruff agents, thickeners, suspending agents, sequestering agents, opacifying agents, colorants, sunscreen agents, fragrances and preservatives.

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8. Process for the permanent deformation of the hair, characterized in that it comprises the application of a reducing composition defined in any one of Claims 1 to 7 comprising, as reducing agent, a compound of formula (I), the hair being shaped by mechanical means and the reducing composition being applied before or after the means for shaping the hair, a setting composition additionally being applied after the reducing composition.

9. Use of a compound of formula (I) according to any one of Claims 1 to 7 as reducing agent for the permanent deformation or the straightening of the hair.

10. Kit comprising, in a first compartment, a composition in accordance with any one of Claims 1 to 7 as reducing composition and, in a second compartment, an oxidizing composition.

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